

Beamline Workshop

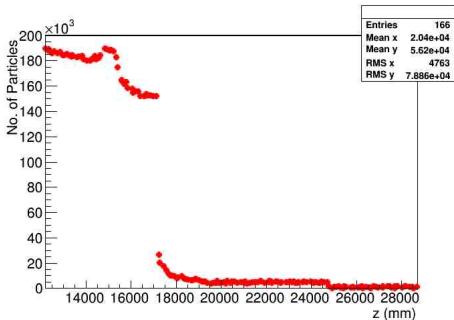
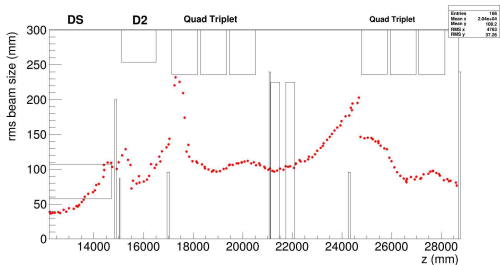
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G4BL Beam Envelope



π Contamination

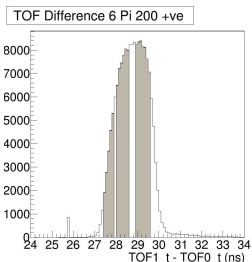


Figure: G4BL TOF (6, 200) μ^+ beam
Table: % π contamination at TOF points

	% π in Point 1	% π in Point 2	% π in Point 3
elevation	1.270 ± 0.009	0.0900 ± 0.0004	0.0400 ± 0.0002
flat	2.00 ± 0.002	0.200 ± 0.006	0.100 ± 0.004

- Contamination for the entire profile is 0.220000 ± 0.000005 %, compare with 0.33 ± 0.03

Beam Size

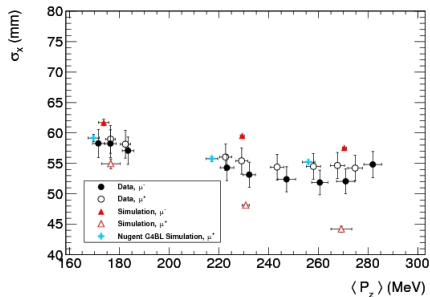


Figure: Horizontal beam size

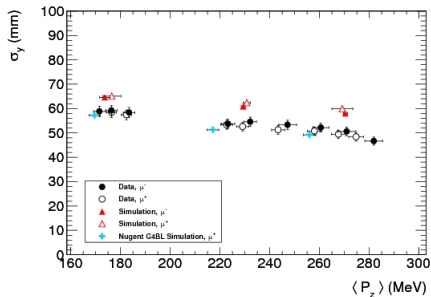


Figure: Vertical beam size

Dispersion

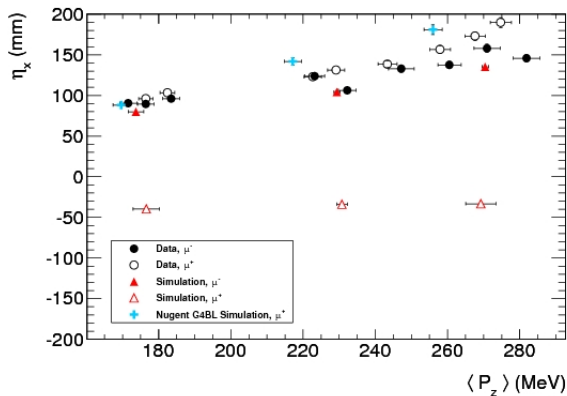


Figure: Horizontal beam dispersion

Emittance

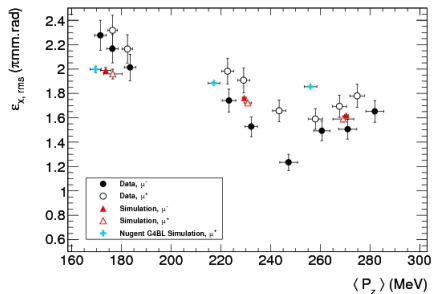


Figure: Horizontal Emittance

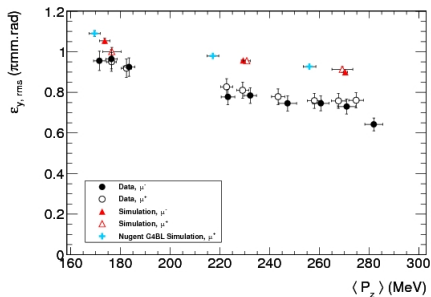


Figure: Vertical Emittance size